

SOLID STATE IMAGING DEVICE

BACKGROUND OF THE INVENTION

The present invention relates to an NMOS solid state imaging device using N-type
5 MOS transistors alone as transistors included therein, and more particularly, it relates to a
technique to include an AD converter in an NMOS solid state imaging device for realizing
a digital signal output function.

FIG. 16 is a block diagram for showing the internal configuration of a conventional CMOS solid state imaging device. As shown in FIG. 16, the CMOS solid
10 state imaging device 10 includes a pixel unit 11 composed of a plurality of pixels 11a
arranged in a matrix, a vertical scanning unit 12 for outputting a row selection signal for
selecting an arbitrary pixel row in the pixel unit 11, and a horizontal scanning unit 13 for
reading an analog signal output from each pixel belonging to the pixel row selected in
accordance with the row selection signal. The vertical scanning unit 12 is connected to
15 each pixel row of the pixel unit 11 through a first selection signal line 11b, and the
horizontal scanning unit 13 is connected to each pixel column of the pixel unit 11 through a
second selection signal line 11c. Also, a noise filtering unit 14 for removing noise from
the analog signal output from each pixel of the pixel unit 11 is provided between the pixel
unit 11 and the horizontal scanning unit 13. Moreover, the CMOS solid state imaging
20 device 10 further includes an amplifier unit 15 for amplifying the analog signal read by the
horizontal scanning unit 13, and an AD converter 16 for converting the analog signal
having been amplified by the amplifier unit 15 into a digital pixel signal and outputting it
to the outside (i.e., to a signal processor 20). The signal processor 20 transmits pulses and
the like necessary for the operations of respective constitution elements of the CMOS solid
25 state imaging device 10.

As compared with the case where an analog pixel signal is output, advantages of outputting a digital pixel signal are, for example, that an interface portion between the solid state imaging device and the signal processor typified by a DSP (Digital Signal Processor) is less influenced by noise and that the signal is less degraded. Therefore, many CMOS solid state imaging devices include AD converters (see, for example, Japanese Laid-Open Patent Publication No. 2000-286706 (pp. 2 – 5 and FIG. 1)).

Apart from conventional CCD solid state imaging devices and CMOS solid state imaging devices, development of NMOS solid state imaging devices has recently been started. In an NMOS solid state imaging device, N-type MOS transistors alone are used as transistors included in its circuits. Specifically, an NMOS solid state imaging device is expected to be a promising solid state imaging device that can be fabricated through a largely reduced number of processes necessary for forming wells and transistors in a substrate while keeping its imaging performances.

FIG. 17 is a block diagram for showing the internal configuration of a conventional NMOS solid state imaging device. As shown in FIG. 17, the NMOS solid state imaging device 30 includes a pixel unit 31 composed of a plurality of pixels 31a arranged in a matrix, a vertical scanning unit 32 for outputting a row selection signal for selecting an arbitrary pixel row in the pixel unit 31, and a horizontal scanning unit 33 for reading an analog signal output from each pixel belonging to the pixel row selected in accordance with the row selection signal. The vertical scanning unit 32 is connected to each pixel row of the pixel unit 31 through a first selection signal line 31b, and the horizontal scanning unit 33 is connected to each pixel column of the pixel unit 31 through a second selection signal line 31c. A noise filtering unit 34 for removing noise from the analog signal output from each pixel of the pixel unit 31 is provided between the pixel unit 31 and the horizontal scanning unit 33. Moreover, the NMOS solid state imaging device

30 further includes an amplifier unit 35 for amplifying the analog signal read by the horizontal scanning unit 33 and outputting the amplified analog signal to the outside (i.e., to a signal processor 40). The signal processor 40 transmits pulses and the like necessary for the operations of respective constitution elements of the NMOS solid state imaging device 30.

5 However, it is very difficult, from the viewpoint of keeping a conversion rate, to provide the NMOS solid state imaging device using N-type MOS transistors alone as transistors with equivalent functions to those of a CMOS solid state imaging device, and particularly to include an AD converter in the NMOS solid state imaging device. 10 Specifically, as shown in FIG. 17, the conventional NMOS solid state imaging device does not include an AD converter. Therefore, although an NMOS solid state imaging device is a promising solid state imaging device as described above, it can disadvantageously exhibit functions poorer than those of a CMOS solid state imaging device.

15 SUMMARY OF THE INVENTION

In consideration of the aforementioned disadvantage, an object of the invention is including, in an NMOS solid state imaging device, a rapid AD converter having a circuit configuration including N-type MOS transistors alone.

In order to achieve the object, the solid state imaging device of this invention 20 using N-type MOS transistors alone as transistors included therein, includes a pixel unit composed of a plurality of pixels arranged in a two-dimensional matrix, each of the pixels including a photoelectric converting element for generating charge in response to light and an amplifying element for outputting, as an analog signal, a voltage signal corresponding to the charge generated by the photoelectric converting element; a selection signal line 25 provided correspondingly to each pixel row of the pixel unit; a comparison/storage unit

provided correspondingly to each pixel column of the pixel unit for converting, into a digital signal, the analog signal output from the amplifying element included in each pixel belonging to a pixel row selected in the pixel unit and for storing the digital signal; a scanner for selecting and reading the digital signal stored in the comparison/storage unit in 5 time series; and an amplifier for amplifying the read digital signal and outputting the amplified digital signal to the outside.

In the NMOS solid state imaging device of this invention, an analog signal output from the amplifying element of each pixel belonging to a pixel row selected in the pixel unit is rapidly converted into a digital signal in the comparison/storage unit. Therefore, 10 the NMOS solid state imaging device can attain an AD conversion function equivalent to that of a CMOS solid state imaging device, and thus, the additional value of the NMOS solid state imaging device can be remarkably improved.

Preferably, in the solid state imaging device, the comparison/storage unit includes a comparator, which includes three inverter circuits using N-type MOS transistors alone 15 and serially connected to one another, and a booster circuit for preventing voltage attenuation of an output signal and accelerating the output signal; in order to increase a fall speed of an inverter circuit disposed at the first stage out of the three inverter circuits, ON resistance of a transistor connected to GND potential is set to be smaller than ON resistance of a transistor connected to power potential in the inverter circuit disposed at the 20 first stage; in order to increase a rise speed of an inverter circuit disposed at the second stage out of the three inverter circuits, ON resistance of a transistor connected to the power potential is set to be smaller than ON resistance of a transistor connected to the GND potential in the inverter circuit disposed at the second stage; and in order to increase a fall speed of an inverter circuit disposed at the third stage out of the three inverter circuits, ON 25 resistance of a transistor connected to the GND potential is set to be smaller than ON

resistance of a transistor connected to the power potential in the inverter circuit disposed at the third stage.

Thus, the comparator is provided with the booster circuit, and the fall speed from “High” level to “Low” level of the ultimate output characteristic of the inverter circuit disposed at the third stage of the comparator is increased. Therefore, even though N-type MOS transistors alone are used, problems of signal voltage level attenuation, consumption power increase and response speed lowering can be prevented.

Preferably, in the solid state imaging device, the comparison/storage unit includes a memory, which includes a first switch for reading a counter value on the basis of a signal supplied from the comparator, a capacitor for storing the read counter value, a second switch for transferring the counter value stored in the capacitor, a third switch for deleting the transferred counter value, a fourth switch for reading the transferred counter value on the basis of a signal supplied from the scanner, and the amplifier for outputting the read counter value to the outside, and the amplifier includes a booster circuit for preventing voltage attenuation of an output signal thereof and accelerating the output signal.

Thus, circuit elements can be shared in accordance with the operation characteristics thereof in the memory, resulting in reducing the circuit scale. Furthermore, since the amplifier is provided with the booster circuit, even though N-type MOS transistors alone are used, the problems of the signal voltage attenuation, the consumption power increase and the response speed lowering can be prevented, so that the NMOS solid state imaging device can attain performances at the practical levels.

Preferably, the solid state imaging device of this invention further includes a pulse generator for generating a pulse signal on the basis of a column selection signal output from a horizontal scanner included in the scanner; and a counter generator for generating the counter value on the basis of the pulse signal generated by the pulse generator.

Thus, a pulse generation circuit included in an external signal processor such as a DSP in a conventional solid state imaging device can be omitted. Also in this case, when the counter generator is provided with a booster circuit for preventing voltage attenuation of its output signal and accelerating the output signal, the problems of the signal voltage level attenuation, the consumption power increase and the response speed lowering can be 5 more definitely prevented.

The solid state imaging device of this invention may further include a ramp waveform generator for generating a ramp signal on the basis of the pulse signal generated by the pulse generator and the counter value generated by the counter generator.

10 The alternative solid state imaging device of this invention includes a pixel unit formed on a semiconductor substrate and outputting, as an analog signal, a voltage signal corresponding to light; and an AD converter formed on the semiconductor substrate and converting the analog signal output from the pixel unit into a digital signal, and transistors included in the pixel unit and the AD converter are all N-type MOS transistors, and the AD 15 converter includes a booster circuit.

In the alternative NMOS solid state imaging device, an analog signal output from the pixel unit is converted into a digital signal in the AD converter. Also, since the AD converter includes the booster circuit, voltage attenuation of its output pulse can be prevented and the output pulse can be accelerated. Therefore, the NMOS solid state 20 imaging device can realize a rapid AD conversion function equivalent to that of a CMOS solid state imaging device, so that the additional value of the NMOS solid state imaging device can be remarkably improved.

Preferably, in the alternative solid state imaging device of this invention, the booster circuit includes a transistor whose source or drain is connected to power potential, 25 and a voltage not less than the power potential is applied to a gate of the transistor.

Thus, the transistor of the booster circuit can be placed in a complete conductive state, and therefore, a signal at "High" level can be output while preventing the voltage attenuation.

Preferably, in the alternative solid state imaging device, the AD converter includes, 5 in addition to the booster circuit, any or all of a comparator, a memory, a pulse generator and a counter generator.

Thus, a rapid AD converter can be definitely obtained.

In the case where the AD converter includes a comparator, the comparator may include an inverter circuit having the booster circuit, the booster circuit may include a first 10 transistor whose source or drain is connected to power potential, and a voltage not less than the power potential may be applied to a gate of the first transistor.

Alternatively, in the case where the AD converter includes a comparator, the comparator may include an inverter circuit having the booster circuit, the inverter circuit may have a second transistor formed above a well region independent of other well regions, 15 and a gate and a source of the second transistor may be electrically connected to the well region.

In the case where the AD converter includes a memory, the memory may include a plurality of switches, a capacitor and an output amplifier, the output amplifier may include a booster circuit, the booster circuit may have a transistor whose source or drain is 20 connected to power potential, and a voltage not less than the power potential may be applied to a gate of the transistor. In this case, the memory may include a first switch for reading a counter value on the basis of a signal supplied from the comparator, a capacitor for storing the read counter value, a second switch for transferring the counter value stored in the capacitor, a third switch for deleting the transferred counter value, a fourth switch for 25 reading the transferred counter value on the basis of a signal supplied from the scanner,

and an output amplifier for outputting the read counter value to the outside.

In the case where the AD converter includes a pulse generator, the pulse generator generates a pulse signal on the basis of a column selection signal output from a horizontal scanner and may include a plurality of inverter circuits serially connected to one another, 5 an inverter circuit disposed at the ultimate stage out of the plurality of inverter circuits may include a booster circuit, the booster circuit may have a transistor whose source or drain is connected to power potential, and a voltage not less than the power potential may be applied to a gate of the transistor.

In the case where the AD converter includes a counter generator, the counter 10 generator generates a counter value on the basis of a pulse signal generated by the pulse generator and may include a plurality of inverter circuits each having a booster circuit, the booster circuit may have a transistor whose source or drain is connected to power potential, and a voltage not less than the power potential may be applied to a gate of the transistor.

In this manner, according to the present invention, the NMOS solid state imaging 15 device is provided with the rapid comparison/storage unit, that is, a rapid AD converter, that converts an analog signal output from the pixel unit into a digital signal and uses N-type MOS transistors alone. Therefore, even the NMOS solid state imaging device can include an AD converter equivalent to that used in a CMOS solid state imaging device, so that the additional value of the NMOS solid state imaging device can be remarkably 20 improved.

In other words, the present invention relates to the technique to include an AD converter in a solid state imaging device, and is particularly useful in application to an NMOS solid state imaging device for realizing a digital signal output function.

BRIEF DESCRIPTION OF THE DRAWINGS

FIG. 1 is a block diagram for showing the schematic configuration of an NMOS solid state imaging device according to an embodiment of the invention;

5 FIG. 2 is a block diagram for showing the schematic circuit configuration of a comparator used in the NMOS solid state imaging device according to the embodiment;

FIG. 3 is a block diagram for showing the detailed circuit configuration of the comparator used in the NMOS solid state imaging device according to the embodiment;

FIG. 4 is an operation timing chart of the comparator used in the NMOS solid state imaging device according to the embodiment;

10 FIG. 5 is a block diagram for showing the schematic circuit configuration of a memory used in the NMOS solid state imaging device according to the embodiment;

FIG. 6 is a block diagram for showing the detailed circuit configuration of the memory used in the NMOS solid state imaging device according to the embodiment;

15 FIG. 7 is an operation timing chart of the memory used in the NMOS solid state imaging device according to the embodiment;

FIG. 8 is a block diagram for showing the circuit configuration of a pulse generator used in the NMOS solid state imaging device according to the embodiment;

FIG. 9 is an operation timing chart of the pulse generator used in the NMOS solid state imaging device according to the embodiment;

20 FIG. 10 is a block diagram for showing the circuit configuration of a counter generator used in the NMOS solid state imaging device according to the embodiment;

FIG. 11 is a block diagram for showing the detailed configuration of a frequency divider used in the counter generator in the NMOS solid state imaging device according to the embodiment;

25 FIG. 12 is an operation timing chart of the counter generator used in the NMOS

solid state imaging device according to the embodiment;

FIG. 13 is a block diagram for showing the circuit configuration of a DA converter used in the NMOS solid state imaging device according to the embodiment;

5 FIG. 14 is a block diagram for showing the circuit configuration of a ramp waveform generator used in the NMOS solid state imaging device according to the embodiment;

FIG. 15 is an operation timing chart of the ramp waveform generator used in the NMOS solid state imaging device according to the embodiment;

10 FIG. 16 is a block diagram for showing the schematic configuration of a conventional CMOS solid state imaging device;

FIG. 17 is a block diagram for showing the schematic configuration of a conventional NMOS solid state imaging device; and

15 FIG. 18 is a cross-sectional view of a transistor used for constructing an inverter circuit included in the comparator used in the NMOS solid state imaging device according to the embodiment.

DETAILED DESCRIPTION OF THE INVENTION

A solid state imaging device according to an embodiment of the invention, and specifically, an NMOS solid state imaging device that uses N-type MOS transistors alone 20 as transistors included in its circuits and includes an AD converter, will now be described with reference to the accompanying drawings.

FIG. 1 is a block diagram for showing the schematic configuration of the NMOS solid state imaging device of this embodiment.

As shown in FIG. 1, the NMOS solid state imaging device 100 includes a pixel 25 unit 101 composed of a plurality of pixels 101a arranged in a two-dimensional matrix, a

vertical scanner 102 for outputting a row selection signal for selecting an arbitrary pixel row in the pixel unit 101, and a horizontal scanner 103 for outputting a column selection signal for selecting an arbitrary pixel column in the pixel unit 101. The vertical scanner 102 is connected to each pixel row of the pixel unit 101 through a first selection signal line 101b, and the horizontal scanner 103 is connected to each pixel column of the pixel unit 101 through a second selection signal line 101c. Although not shown in the drawing, each pixel 101a of the pixel unit 101 includes a photoelectric converter (such as a photo diode) for generating charge in response to light and an amplifier (such as an amplifier transistor) for outputting, as an analog signal, a voltage signal corresponding to the charge generated by the photoelectric converter.

As a characteristic of this embodiment, a comparison/storage unit (i.e., a comparator 104 and a memory 105) is provided between the pixel unit 101 and the horizontal scanner 103 correspondingly to each pixel column of the pixel unit 101. The comparison/storage unit converts an analog signal output from the amplifier of each pixel 101a belonging to the pixel row selected in the pixel unit 101 into a digital signal and stores the digital signal. Specifically, the comparator 104 reads an analog signal from each pixel 101a belonging to the pixel row selected in accordance with the row selection signal, and synthesizes the read analog signal with a ramp signal so that the synthesized signal can be compared with a reference voltage. Also, the memory 105 accepts, as an input, the comparison result obtained by the comparator 104, and stores a counter value on the basis of the comparison result and reads, as a digital signal, the stored counter value in time series on the basis of the column selection signal. As described later, the memory 105 includes an amplifier for amplifying the digital signal and outputting the amplified digital signal to the outside (i.e., to a signal processor 150).

As another characteristic of this embodiment, the NMOS solid state imaging

device 100 further includes a pulse generator 106 for generating a pulse signal on the basis of the column selection signal supplied by the horizontal scanner 103; a counter generator 107 for generating the counter value necessary for the memory 105 on the basis of the pulse signal supplied by the pulse generator 106; a DA converter 108 for generating an 5 analog signal on the basis of the counter value supplied by the counter generator 107; and a ramp waveform generator 109 for generating the ramp signal necessary for the comparator 104 on the basis of the analog signal supplied by the DA converter 108 and the pulse signal supplied by the pulse generator 106. The pulse generator 106 transmits the pulse signal also to the pixel unit 101, the vertical scanner 102, the comparator 104 and the memory 10 105. Also, the signal processor 150 provided outside the NMOS solid state imaging device 100 transmits given signals to the horizontal scanner 103 and the counter generator 107.

In this manner, the comparator 104, the memory 105, the pulse generator 106 and the counter generator 107 together form an AD converter in this embodiment, but the 15 configuration of the AD converter is not limited to this. For example, there is no need for the AD converter to include all of the comparator 104, the memory 105, the pulse generator 106 and the counter generator 107. Also, as described later, the AD converter preferably includes a booster circuit.

Now, the respective constitution elements of the NMOS solid state imaging device 20 100, that is, specifically, the comparator 104, the memory 105, the pulse generator 106, the counter generator 107, the DA converter 108 and the ramp waveform generator 109, will be described in detail. As a premise of the following description, the respective constitution elements (such as the pixel unit and the AD converter) of the NMOS solid state imaging device 100 are formed on one and the same chip (namely, on one 25 semiconductor substrate).

First, the comparator 104 will be described. As shown in FIG. 1, the comparator 104 generates the synthesized signal from the analog pixel signal output from each column of the pixel unit 101 and the ramp signal output from the ramp waveform generator 109, compares the synthesized signal with the reference voltage generated within the 5 comparator 104 and rapidly transfers the comparison result to the memory 105. Transistors included in the comparator 104 are N-type MOS transistors alone, and in this embodiment, in order to prevent problems of signal voltage level attenuation, power consumption increase, response speed lowering and the like peculiar to a circuit composed of N-type MOS transistors, the comparator 104 is provided with circuital specific means as 10 follows: The comparator 104 uses three inverter circuits connected in series to one another. In this case, among the three inverter circuits, one disposed at the input initial stage (namely, the first stage) is designed, in order to increase its fall speed, so that the ON resistance of a transistor connected to GND potential can be relatively small and the ON 15 resistance of a transistor connected to power potential can be relatively large. Also, the inverter circuit disposed at the second stage is designed, in order to increase its rise speed, so that the ON resistance of a transistor connected to power potential can be relatively small and the ON resistance of a transistor connected to GND potential can be relatively large. In addition, the inverter circuit disposed at the third stage is designed, in order to increase its fall speed, so that the ON resistance of a transistor connected to GND potential 20 can be relatively small and the ON resistance of a transistor connected to power potential can be relatively large. Furthermore, in order to prevent the voltage attenuation of its output pulse and to accelerate the output pulse, the comparator 104 includes a booster circuit. Since the circuit is thus designed with emphasis placed on the increase of the fall speed from "High" level to "Low" level of the ultimate output characteristic of the inverter 25 circuit disposed at the third stage, even though N-MOS transistors alone are used in the

circuit, the signal voltage level can be kept, the consumption power can be reduced and the response speed can be increased so as to attain performances at practical levels.

FIG. 2 is a block diagram for showing an example of the circuit configuration (of a portion corresponding to six pixel columns) of the comparator 104 of this embodiment, 5 FIG. 3 is a block diagram for showing the detailed circuit configuration of a portion corresponding to one pixel column of the comparator 104 of FIG. 2, and FIG. 4 is an operation timing chart of the comparator 104 of FIG. 2. In FIGS. 2 and 3, M19 through M29 indicate N-type MOS transistors, C20 through C23 indicate capacitors and I21 through I23 indicate inverter circuits.

10 As shown in FIGS. 2 through 4, in the comparator 104, first, when a pixel signal input switch SIGSW is set to “High” level with an analog pixel signal SIG held at a reset level in a horizontal blanking period, the transistor M20 is turned on so as to input the pixel signal SIG at the reset level. Next, when a comparator reset switch CMPRS is set to “High” level, the transistor M22 is turned on so as to remove threshold variation of the 15 transistor M23 and threshold variation of the amplifier transistors of the respective pixels, and then, the pixel signal SIG is read from the photodiode of each pixel. Thereafter, when a ramp signal input switch SAWSW is set to “High” level, the transistor M19 is turned on so as to input a ramp signal, and thus, a synthesized signal of the ramp signal and the pixel signal SIG is allowed to appear on a node VIN (see FIG. 3). At this point, the 20 ramp waveform is adjusted so that the initial value of the voltage on the node VIN can be always lower than the threshold variation of the transistor M23. Subsequently, as the ramp signal is linearly swept, the voltage on the node VIN also increases, and when the voltage on the node VIN becomes higher than the threshold voltage of the transistor M23, potential on a node N22 becomes “Low” level, potential on a node N24 becomes “High” 25 level and a comparator output signal CMPOUT undergoes a “Low” transition.

Significant points to be realized by the comparator 104 are that "High" level corresponding to the initial value of the comparator output signal **CMPOUT** is power voltage (power potential) level, and that the fall speed of the comparator output signal **CMPOUT** from "High" level to "Low" level is as fast as possible. This is because, in the 5 memory 105 (see FIG. 5) disposed at the subsequent stage of the comparator 104, an N-type MOS transistor **M30** is controlled in accordance with the comparator output signal **CMPOUT** so as to store a counter value.

Therefore, in this embodiment, the dimensions of the three stages of inverter circuits **I21** through **I23** all using N-MOS transistors alone is devised. Specifically, the 10 inverter circuits are designed with emphasis placed on the fall characteristic in the inverter circuit **I21** disposed at the first stage, with emphasis placed on the rise characteristic in the inverter circuit **I22** disposed at the second stage, and with emphasis placed on the fall characteristic in the inverter circuit **I23** disposed at the third stage.

More specifically, in the inverter circuit **I21** disposed at the first stage, the ON 15 resistance of the transistor **M23** is reduced by making the gate length relatively small and the gate width relatively large in the transistor **M23** used for driving to "Low" level, and thus, the fall speed of the inverter circuit **I21** disposed at the first stage can be increased. On the other hand, the ON resistance of the transistor **M21** is increased by making the gate length relatively large and the gate width relatively small in the transistor **M21** used for 20 driving to "High" level, and thus, the current is reduced. Since the transistor **M21** of the inverter circuit **I21** is a depletion type transistor, the "High" potential in the inverter circuit **I21** disposed at the first stage and provided with the booster circuit is the same as the power potential (i.e., the power voltage **VDD**). FIG. 18 is a cross-sectional view of the transistor **M21** included in the inverter circuit **I21** disposed at the first stage. As shown in 25 FIG. 18, in a semiconductor substrate 200 of the same conductivity type as that of the

transistor **M21**, namely, a semiconductor substrate **200** on which the NMOS solid state imaging device **100** of this embodiment is built, wells **201** and **202** of a conductivity type different from that of the semiconductor substrate **200** are formed. In this case, the well **202** is independent of the well **201**. Also, an N-type MOS transistor other than the 5 transistor **M21** is formed above the well **201**, and the transistor **M21** alone is formed above the well **202**. Specifically, a gate electrode **206** is formed above the well **202** with an insulating film **203** sandwiched therebetween. Also, on both sides of the gate electrode **206** in the well **202**, a drain region **204** and a source region **205** are formed. Furthermore, the source region **205** and the gate electrode **206** of the transistor **M21** are set to have the 10 same potential as the well **202** through an interconnect **207**. Although not shown in the drawing, the source region **205** and the gate electrode **206** are connected to the drain of the transistor **M23** through the interconnect **207**. Furthermore, the drain region **204** of the transistor **M21** is connected to the power source through an interconnect **208**.

Also, in the inverter circuit **I22** disposed at the second stage, the ON resistance of 15 the transistor **M25** is reduced by making the gate length relatively small and the gate width relatively large in the transistor **M25** used for driving to “High” level. Furthermore, when the inverter **I21** disposed at the first stage outputs a signal at “High” level, the transistor **M24** is turned on so that a voltage obtained by subtracting the threshold voltage of the transistor **M24** from the power potential **VDD** can be applied to the gate of the transistor 20 **M25**. Moreover, when the inverter circuit **I21** outputs a signal at “Low” level, a voltage boosted to exceed the power voltage **VDD** is applied to the gate of the transistor **M25**, and hence the transistor **M25** becomes completely conductive. In other words, the inverter circuit **I22** is provided with the booster circuit having the transistor **M25** whose source or drain is connected to the power potential **VDD**. As a result, the rise speed of the inverter 25 circuit **I22** disposed at the second stage can be increased without causing the voltage

attenuation. On the other hand, the ON resistance of the transistor **M26** is increased by making the gate length relatively large and the gate width relatively small in the transistor **M26** used for driving to “Low” level, and thus, the current is reduced.

Moreover, in the inverter circuit **I23** disposed at the third stage, the ON resistance of the transistor **M29** is reduced by making the gate length relatively small and the gate width relatively large in the transistor **M29** used for driving to “Low” level, and thus, the fall speed of the inverter circuit **I23** disposed at the third stage is increased. On the other hand, the ON resistance of the transistor **M28** is increased by making the gate length relatively large and the gate width relatively small in the transistor **M28** used for driving to “High” level, and thus, the current is reduced. It is noted that a voltage obtained by subtracting the threshold voltage of the transistor **M27** from the power potential **VDD** is applied to the gate of the transistor **M28** in order to output a signal at “High” level without attenuating it to be smaller than the power potential **VDD**. Also, when the inverter circuit **I22** disposed at the second stage outputs a signal at “Low” level, a voltage boosted to exceed the power potential **VDD** is applied to the gate of the transistor **M28**, and hence, the transistor **M28** becomes completely conductive. In other words, the inverter circuit **I23** is provided with the booster circuit having the transistor **M28** whose source or drain is connected to the power potential **VDD**. In this manner, a signal at “High” level can be output without causing the voltage attenuation.

Through the circuit design described above, the fall speed of the comparator output signal **CMPOUT** of the comparator **104** can be improved and the power consumption of the comparator **104** can be reduced.

Next, the memory **105** will be described. As shown in FIG. 1, the memory **105** interrupts the counter value input from the counter generator **107** in accordance with a “Low” signal output as a result of the comparison operation of the comparator **104**, and

stores the counter value input at the interruption in a counter value storage capacitor. Also, the memory **105** reads the stored counter value in time series in accordance with the pulse (the column selection signal) supplied from the horizontal scanner **103** and successively outputs the read counter value through an output amplifier to the outside (the 5 signal processor **150**) as a digital signal. At this point, since transistors included in the memory **105** are all N-type MOS transistors as in the comparator **104**, the memory **105** includes a booster circuit in order to prevent the problems of the signal voltage level attenuation, the consumption power increase and the response speed lowering, so as to attain performances at the practical levels. Furthermore, in order to reduce the circuit 10 scale, circuit elements included in the memory **105** are shared as much as possible on the basis of the characteristics of their operations.

FIG. 5 is a block diagram for showing an example of the circuit configuration (of a portion corresponding to six pixel columns) of the memory **105** of this embodiment, FIG. 6 is a block diagram for showing the detailed circuit configuration of a portion 15 corresponding to one pixel column of the memory **105** of FIG. 5, and FIG. 7 is an operation timing chart of the memory **105** of FIG. 5. In FIGS. 5 and 6, **M30** through **M34** and **M40** through **M48** indicate N-type MOS transistors, **C30** and **C40** through **C43** indicate capacitors, **Lat** indicates a latch circuit and **AMP** indicates an amplifier.

As shown in FIGS. 5 through 7, in the latch circuit **Lat** of the memory **105**, first, 20 when the comparator output signal **COMPOUT** from the comparator **104** undergoes a “Low” transition in a horizontal blanking period, the transistor **M30** is turned off, so that a counter code (a digital value) supplied from the counter generator **107** can be sampled to be pre-fetched by the pre-fetching capacitor **C30**. Next, when a latch data transfer signal **DATATR** undergoes a “High” transition, the transistor **M31** is turned on, so that the pre-fetched counter code can be applied to the gate of the transistor **M34**. In this manner, 25

data reversed to the counter code data (namely, inverted data) appears on the drain (on the side of the transistor **M33**) of the transistor **M34**. A pulse (a column selection signal **HSR**) supplied from the horizontal scanner **103** is successively applied to the gate of the transistor **M33**, and as a result, the inverted data of the pre-fetched counter code is input as 5 a time series signal to the amplifier **AMP** that outputs inverted data. After the inverted data of the counter code is input to the amplifier **AMP**, a data clear signal **DATACLR** undergoes a “High” transition so as to clear charge of each pre-fetching capacitor **C30**, and the transistor **M32** is turned on.

Next, in the amplifier **AMP** provided in the memory **105** for externally outputting 10 a digital value resulting from AD conversion, an operation start pulse (an inverter start 1 signal) **INVSTA1** for operating an inverter circuit disposed at the first stage is turned on, and subsequently, an operation start pulse (an inverter start 2 signal) **INVSTA2** for operating an inverter circuit disposed at the second stage is turned on. Thus, the amplifier **AMP** can be previously placed in an operation state. At this point, as described above, 15 the transistor **M33** is turned on through the “High” transition of the column selection signal **HSR** supplied from the horizontal scanner **103** and the pre-fetched counter code is input to the amplifier **AMP** through the transistor **M33** as a digital signal. In this manner, the digital signal obtained by converting the analog pixel signal is ultimately amplified by the amplifier **AMP** to be output to the outside. In the amplifier **AMP**, the consumption 20 power can be reduced by using an inverter operation stop pulse (an inverter stop signal) **INVSTP** when the amplifying operation is not necessary. Furthermore, since the inverter circuit included in the amplifier **AMP** has a booster circuit, “High” level can be set to the power potential, and hence, the voltage attenuation of the output signal can be prevented 25 and the output signal can be accelerated. The specific operation of the booster circuit is as follows: When the inverter start 1 signal **INVSTA1** is turned on, voltages respectively

obtained by subtracting the threshold voltages of the transistors **M40** and **M43** from the power potential **VDD** are respectively applied to the gates of the transistors **M41** and **M44** included in the booster circuit of each inverter circuit. When potential at the gate of the transistor **M34** becomes “Low”, a voltage boosted to exceed the power potential **VDD** is applied to the gate of the transistor **M41**, and therefore, the transistor **M41** becomes completely conductive. Accordingly, a signal at “High” level can be output without causing the voltage attenuation. Similarly, when potential at the gate of the transistor **M34** becomes “High”, a voltage boosted to exceed the power potential **VDD** is applied to the gate of the transistor **M44**, and therefore, the transistor **M44** becomes completely conductive. Therefore, a signal at “High” level can be output without causing the voltage attenuation. The source or the drain of each of the transistors **M41** and **M44** is connected to the power potential **VDD**.

When the above-described booster circuit is used, the rise speed for outputting a signal at “High” level can be easily increased, but the fall speed for outputting a signal at “Low” level is difficult to increase. Therefore, in this embodiment, the gate lengths of the transistor **M34** for driving the output of the latch circuit **Lat** to “Low” level and the transistor **M46** for driving the output of the amplifier **AMP** to “Low” level are made relatively small, and the gate widths of these transistors **M34** and **M46** are made relatively large. Thus, the ON resistances of these transistors are reduced, so that the fall speed can be increased.

Next, the pulse generator **106** will be described. As shown in FIG. 1, the pulse generator **106** generates a timing pulse necessary for the AD conversion through synthesis of the output pulse (the column selection signal) supplied from the horizontal scanner **103**, and inputs the generated pulse to the counter generator **107** disposed at the subsequent stage.

FIG. 8 is a block diagram for showing an example of the circuit configuration of the pulse generator 106 of this embodiment, and FIG. 9 is an operation timing chart of the pulse generator 106 of FIG. 8. In FIGS. 8 and 9, M1 through M4 indicate N-type MOS transistors and C1 indicates a capacitor.

5 As shown in FIGS. 8 and 9, the pulse generator 106 of this embodiment generates a new pulse by using fall edges of two kinds of pulses output in time series from the horizontal scanner 103. Also, the pulse generator 106 includes a plurality of inverter circuits (that is, inverter circuits of two stages in this embodiment) connected in series to one another, and a booster circuit is provided to the inverter circuit at the ultimate stage out 10 of the plural inverter circuits. Specifically, in the pulse generator 106, when an input signal INPUT1 supplied from the horizontal scanner 103 undergoes a "High" transition, the transistor M1 is turned on, and therefore, a voltage [the power potential VDD – the threshold voltage of the transistor M1] is applied to the bootstrap capacitor C1 to charge the capacitor C1 and this voltage is also applied to the gate of the transistor M3. 15 Therefore, a voltage [the power potential VDD – the threshold voltage of the transistor M3] appears as an output signal OUTPUT of the pulse generator 106. Thus, a voltage on a node N1 is boosted, and the boosted voltage is applied to the gate of the transistor M3. In other words, a voltage not less than the power potential VDD is applied to the gate of the transistor M3 that is included in the booster circuit and is connected to the power 20 potential VDD at its source or drain. Therefore, a "High" signal at the level of the power potential VDD appears as the output signal OUTPUT. On the other hand, when an input signal INPUT2 supplied from the horizontal scanner 103 undergoes a "High" transition, the transistors M2 and M4 are turned on. Therefore, the potential on the node N1 and the output signal OUTPUT are driven to GND level, so that a "Low" signal appears as the 25 output signal OUTPUT. Through this operation principle, the pulse generates 106

generates, from the pulse supplied from the horizontal scanner 103, pulses necessary for the AD conversion and the counter code generation.

Next, the counter generator 107 will be described. As shown in FIG. 1, the counter generator 107 accepts, as inputs, the output pulse from the horizontal scanner 103 and the pulse generated by the pulse generator 106, generates data (a counter value) working as a digital output value resulting from the AD conversion and outputs the generated data to the memory 105.

FIG. 10 is a block diagram for showing an example of the circuit configuration of the counter generator 107 using frequency divider circuits of this embodiment, FIG. 11 is a block diagram for showing the configuration of one frequency divider circuit of the counter generator 107 of FIG. 10, and FIG. 12 is an operation timing chart of the counter generator 107 of FIG. 10. In FIG. 11, M51 through M74 indicate N-type MOS transistors and C51 through C54 indicate capacitors.

As shown in FIGS. 10 through 12, the operation of the counter generator 107 is first started by using the pulse generated by the pulse generator 106 and a reference pulse input from the signal processor 150 to the horizontal scanner 103. Then, when a pulse to be divided is input while a division start pulse input **CODE_nSTA** (n = 0 through 9) is at “High” level, a signal whose polarity is inverted in synchronization with the pulse to be divided appears as a divide-by-2 subharmonic pulse output **CODE_n** (n = 0 through 9). Next, when the pulse to be divided is input with the division start pulse input **CODE_nSTA** placed at “Low” level, the signal whose polarity is inverted in synchronization with the pulse to be divided appears again as the divide-by-2 subharmonic pulse output **CODE_n**. In the counter generator 107, the frequency divider circuits each having the configuration shown in FIG. 11 are cascaded so as to generate the counter value necessary for the AD conversion through the above-described operation principle.

The frequency divider circuit shown in FIG. 11 contains a plurality of inverter circuits each including a booster circuit. The operation of this booster circuit is as follows: Voltages respectively obtained by subtracting the threshold voltages of the transistors **M52**, **M56** and **M59** from the power potential **VDD** are previously applied respectively to the gates of the transistors **M53**, **M57** and **M60** that are included in the booster circuit and are connected to the power potential **VDD** at their sources or drains. Then, when potentials at the gates of the transistors **M54**, **M58** and **M61** respectively disposed on the drive sides of the transistors **M53**, **M57** and **M60** are at "Low" level, voltages boosted to exceed the power potential **VDD** are applied to the gates of the transistors **M53**, **M57** and **M60**, and therefore, the transistors **M53**, **M57** and **M60** become completely conductive. Thus, a signal at "High" level can be output without causing the voltage attenuation.

When the above-described booster circuit is used, the rise speed for outputting a signal at "High" level can be easily increased, but the fall speed for outputting a signal at "Low" level is difficult to increase. Therefore, in this embodiment, the gate lengths of the transistors **M54**, **M58** and **M61** for driving the outputs of the respective inverter circuits of the frequency divider circuit of FIG. 11 to "Low" level are made relatively small, and the gate widths of these transistors **M54**, **M58** and **M61** are made relatively large. Thus, the ON resistances of these transistors are reduced, so that the fall speed can be increased.

Next, the DA converter **108** and the ramp waveform generator **109** will be described. As shown in FIG. 1, the DA converter **108** accepts, as an input, the code data (the counter value) generated by the counter generator **107** and generates an analog signal. Also, the ramp waveform generator **109** accepts, as inputs, an analog signal generated by the DA converter **108** and the pulse generated by the pulse generator **106**, and generates a ramp signal necessary for the comparator **104**. In this case, transistors included in the DA

converter 108 and the ramp waveform generator 109 are all N-type MOS transistors.

FIG. 13 is a block diagram for showing an example of the circuit configuration of the DA converter 108 of this embodiment, FIG. 14 is a block diagram for showing an example of the circuit configuration of the ramp waveform generator 109 of this embodiment, and FIG. 15 is an operation timing chart of the ramp waveform generator 109 of FIG. 14. In FIG. 13, M80 through M89 indicate N-type MOS transistors, I80 through I89 indicate inverter circuits, and R and 2R are resistors. Also, in FIG. 14, M90 through M93 indicate N-type MOS transistors, C90 and C91 indicate capacitors, and V90 and V91 indicate power sources.

First, as shown in FIG. 13, each bit of the counter value (the code data **CODEn**) generated by the counter generator 107 is input to the DA converter 108. Also, the DA converter 108 is an R-2R type DA converter, and hence outputs potential in proportion to the counter value as an analog out signal **ANAOUT**. The analog out signal **ANAOUT** has a linearly sweeping waveform such as a saw tooth wave (see FIG. 15). Subsequently, in the ramp waveform generator 109 shown in FIG. 14, a pulse (a reset pulse) generated by the pulse generator 106 and the analog out signal **ANAOUT** generated by the DA converter 108 are applied at timing shown in FIG. 15, so as to generate a ramp signal having a waveform necessary for the AD conversion. Specifically, first, charge of the capacitor C90 is cleared by using the reset switch (transistor) M91, and at the same time, the DC clamp switch (transistor) M92 is turned on so as to once keep the signal level of the ramp signal at potential of the power source V90. Next, the offset level setting switch (transistor) M93 is turned on so as to keep the output level of the ramp signal at potential of the power source V91. Then, after the reset switch (transistor) M91 is turned off, the analog out switch (transistor) M90 is turned on. Thus, a linearly sweeping waveform similar to the analog out signal **ANAOUT** appears on the basis of the offset level as the

ramp signal output.

As described so far, according to the NMOS solid state imaging device of this embodiment, the design of the respective constitution elements (such as the comparator 104 and the memory 105) is optimized by using N-type MOS transistors alone as transistors included therein, so as to convert an analog signal output from the amplifier included in each pixel 101a belonging to a pixel row selected in the pixel unit 101 into a digital signal. In other words, the AD converter using N-type MOS transistors alone as transistors included therein can be contained in the NMOS solid state imaging device. Therefore, an NMOS solid state imaging device capable of digital output can be realized, resulting in remarkably improving the additional value of the NMOS solid state imaging device.

Furthermore, according to the NMOS solid state imaging device of this embodiment, the booster circuit is provided in the comparator 104, and the fall speed from “High” level to “Low” level of the ultimate output characteristic of the inverter circuit I23 disposed at the third stage of the comparator 104 is increased. Accordingly, even though N-type MOS transistors alone are used, the problems of the signal voltage level attenuation, the consumption power increase and the response speed lowering can be prevented.

Moreover, according to the NMOS solid state imaging device of this embodiment, the circuit elements are shared in accordance with their operation characteristics in the memory 105, and therefore, the circuit scale can be reduced. Also, since the booster circuit is provided in the amplifier AMP included in the memory 105, even though N-type MOS transistors alone are used, the problems of the signal voltage level attenuation, the consumption power increase and the response speed lowering can be prevented. As a result, the NMOS solid state imaging device can attain performances at the practical levels.

In addition, since the NMOS solid state imaging device of this embodiment

includes the pulse generator **106** for generating a pulse signal on the basis of a column selection signal output by the horizontal scanner **103**, a pulse generation circuit included in a signal processor such as a DSP externally provided to a conventional solid state imaging device can be omitted.

5 Furthermore, according to the NMOS solid state imaging device of this embodiment, since the counter generator **107** for generating a counter value includes the booster circuit for preventing the voltage attenuation of the output signal and accelerating the output signal, the problems of the signal voltage level attenuation, the consumption power increase and the response speed lowering can be more definitely prevented.

10 Although the comparator **104** and the memory **105** are separately provided in this embodiment, a comparison/storage unit having both the functions of the comparator and the memory can be provided instead.

 Although the amplifier **AMP** is provided as a part of the memory **105** in this embodiment, the amplifier **AMP** may be provided separately from the memory **105** instead.

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